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IN	THE UNITE	D STATES	PATENT .	AND	TRADEMA	RK OFF	ICE	
	BEFORE T	HE PATEN	T TRIAL .	AND	APPEAL	BOARD		
TAIWA	AN SEMICON	DUCTOR						
MANUF	FACTURING	COMPANY,	LTD.					
AND T	ISMC NORTH	AMERICA	CORP.,	Ca	ase Nos.			
				II	PR2014-0	0781		
		Petition	ners,	II	PR2014-0	0782		
				II	PR2014-0	1083		
-vs-				II	PR2014-0	1086		
				II	PR2014-0	1087		
ZOND,	, LLC,							
		Patent (Owner.					
	VIDEOTAP	ED DEPOSI	ITION of	DR	. UWE KC	RTSHAGI	ΞN	
			VOLUME	I				
		Minnea	polis, M	inne	esota			
		Decer	mber 3rd	, 20	014			
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	ted by:	ייחי						
	Larson,	KPK						
αου	No. 87857							

		Page	2			Page
1	APPEARANCES:	-		1	APPEARANCES: (CONT'D.)	-
2	RADULESCU			2	WHITE & CASE	
	350 Fifth Avenue				701 Thirteenth Street, N.W.	
3	New York, New York 10118			3	Washington, D.C. 20005	
4	By: Etai Lahav, Esq.			4	By: David Tennant, Esq.	
4	Maria Granovsky, Esq. For: Zond, LLC			4	By: Brett Rismiller, Esq. For: Global Foundries	
5	Tor. Zond, ELC			5	Tor. Global Foundries	
6				6		
	GONSALVES LAW FIRM			7		
7	2216 Beacon Lane			8		
	Falls Church, Virginia 22043			9		
8	By: Gregory Gonsalves, Esq.			10		
~	For: Zond, LLC			1 1	O'MELVENY & MYERS	
9 0	DUANE MORRIS			11	400 South Hope Street Los Angeles, California 90071	
0	100 High Street			12	By: Vincent Zhou, Esq. (By telephone)	
1	Boston, Massachusetts 02110			10	For: Advanced Micro Devices	
	By: Anthony Fitzpatrick, Esq.			13		
2	For: Taiwan Semiconductor Manufacturing			14		
	Company Limited and				FOLEY & LARDNER	
3	TSMC North America			15	321 North Clark Street	
4					Chicago, Illinois 60654	
5	HAYNES AND BOONE			16	By: Michael Houston, Esq. (By telephone)	
s	2323 Victory Avenue Dallas, Taxas, 75210			17	For: Renesas Electronics Corporation and	
б	Dallas, Texas 75219 By: David McCombs, Esq.			17 18	Renesas Electronics America, Inc.	
7	By: David McCombs, Esq. By: Gregory Huh, Esq.			10 19	BAKER BOTTS	
-	For: Taiwan Semiconductor Manufacturing				One Shell Plaza	
8	Company Limited and			20	910 Louisiana Street	
	TSMC North America				Houston, Texas 77002	
9				21	By: Michael Silliman, Esq.	
C					For: Toshiba	
1				22		
2				23		
3 4				24	ALSO DESENT: Deen Hibben Videographer	
4 5	///			25	ALSO PRESENT: Dean Hibben, Videographer	
-		Page	4			Page
		10.90	-	-		1090
	INDEX: EXAMINATION BY: PAGE			1	INDEX: (CONT'D.)	
	Mr. Lahav9			2	PREVIOUSLY MARKED EXHIBITS:	
	EXHIBITS MARKED FOR IDENTIFICATION:			3	Exhibit TSMC 1216	
	Exhibit 200495				U.S. Patent 6,306,265 B1	
	U.S. Patent No. 6,398,929 B1			4	No Bates	
	No Bates			5	Exhibit TSMC 1221	
	PREVIOUSLY MARKED EXHIBITS:			5		
	Exhibit TSMC 1001			~	U.S. Patent 5,247,531	
	U.S. Patent No. 6,853,142 B2			6	No Bates	
	No Bates			7	Exhibit TSMC 1222	
	Exhibit INTEL 1002				European Patent Application	
	Kortshagen Declaration - '759 Patent			8	No Bates	
	No Bates Exhibit TSMC 1003			9	Exhibit TSMC 1302	
ا ک ۱	Exhibit ISMC 1003 High-Current Low-Pressure Quasi-Stationary				Kortshagen Declaration - '759 Patent	
	Discharge in a Magnetic Field			10	No Bates	
	Experimental Research					
	No Bates			11	Exhibit	
	Exhibit TSMC 1004				Paper 13 - No Bates	
	U.S. Patent No. 6,190,512 B1			12		
5]	No Bates			13		
	Exhibit TSMC 1201			14		
	U.S. Patent No. 7,147,759 B2			15		
	No Bates			16		
	Exhibit TSMC 1202					
	Kortshagen Declaration - '142 Patent			17		
	No Bates			18		
	Exhibit TSMC 1204 Ionization Relaxation in a plasma produced			19		
	by a pulsed inert-gas discharge			20		
	No Bates			21		
	to 2 mot			22		
3	Exhibit TSMC 1205			22 23		
3	LAMOR ISING 1205			43		
]	U.S. Patent 6,413,382 B1					
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2 (Pages 2 to 5)

1 2	Page 6	5	Page 7
2	THE VIDEOTAPED DEPOSITION OF DR. UWE KORTSHAGE	N, 1	DR. UWE KORTSHAGEN
	VOLUME I, taken on this 3rd day of December, 2014,	2	Avenue, New York, New York. The court
3	at The Commons Hotel, 615 Washington Avenue, S.E.,	3	reporter is Amy Larson in association
4	Minneapolis, Minnesota, commencing at	4	with TSG Reporting.
5	approximately 7:37 a.m.	5	Will counsel please introduce yourselves.
6		6	MR. LAHAV: Etai Lahav of
7	P R O C E E D I N G S	7	Radulescu, LLP, representing the patent owner
8		8	Zond.
9	THE VIDEOGRAPHER: This is the	9	MS. GRANOVSKY: Maria Granovsky,
10	start of tape number 1 in the videotaped	10	Radulescu, LLP, representing Zond.
11	deposition of Dr. Uwe Kortshagen in the	11	MR. GONSALVES: Greg Gonsalves
12	matter of Taiwan Semiconductor Manufacturing	12	representing Zond.
13	Company, LL LTD, et al. Versus Zond, LLC,	13	MR. FITZPATRICK: Anthony
14	in the United States Patent and Trademark	14	Fitzpatrick from Duane Morris, LLP,
15	Office before the Patent Trial and Appeal	15	representing Taiwan Semiconductor
16	Board, case numbers IPR 2014-00781,	16	Manufacturing Company Limited and TSMC
17	IPR 2014-00782, IPR 2014-01083,	17	North America.
18	IPR 2014-01086, and IPR 2014-01087.	18	MR. TENNANT: David Tennant with
19	This deposition is being held at the	19	White & Case representing Global Foundries.
20	Commons Hotel in Minneapolis, Minnesota, on	20	MR. MCCOMBS: David McCombs with
21	December 3rd, 2014, at approximately	21	Haynes & Boone representing TSMC
22	7:41 a.m.	22	North America and Taiwan Semiconductor
23	My name is Dean Hibben, I'm the legal	23	Limited and Fujitsu.
24	video specialist from TSG Reporting,	24	MR. HUH: Gregory Huh with
25	Incorporated, headquartered at 747 Third	25	Haynes & Boone representing TSMC and Fujitsu.
	Page 8	3	Page 9
1	DR. UWE KORTSHAGEN	1	DR. UWE KORTSHAGEN
2	MR. RISMILLER: Brett Rismiller	2	MR. FITZPATRICK: Before we begin
3	with White & Case representing Global	3	the questioning this morning, I did want to
4	Foundries.	4	state on the record that objections that I
	THE VIDEOGRAPHER: And those on	5	
5			make or that Mr. Tennant makes will apply to
5 6	the phone, please.	6	make or that Mr. Tennant makes will apply to all petitioners, to avoid having us
	the phone, please. MR. ZHOU: Yes, this is Xin-Yi		all petitioners, to avoid having us
б		6	
6 7	MR. ZHOU: Yes, this is Xin-Yi	6 7	all petitioners, to avoid having us having to make duplicate objections.
6 7 8	MR. ZHOU: Yes, this is Xin-Yi Zhou. It's spelled X-I-N dash Y-I, and the	6 7 8	all petitioners, to avoid having us having to make duplicate objections. MR. LAHAV: And we agree with
6 7 8 9	MR. ZHOU: Yes, this is Xin-Yi Zhou. It's spelled X-I-N dash Y-I, and the last name is Z-H-O-U, and I represent	6 7 8 9	all petitioners, to avoid having us having to make duplicate objections. MR. LAHAV: And we agree with that. And if we could actually limit it to
6 7 8 9 10	MR. ZHOU: Yes, this is Xin-Yi Zhou. It's spelled X-I-N dash Y-I, and the last name is Z-H-O-U, and I represent Advanced Micro Devices, Inc.	6 7 8 9 10	all petitioners, to avoid having us having to make duplicate objections. MR. LAHAV: And we agree with that. And if we could actually limit it to statements from Mr. Fitzpatrick that would be
6 7 8 9 10 11	MR. ZHOU: Yes, this is Xin-Yi Zhou. It's spelled X-I-N dash Y-I, and the last name is Z-H-O-U, and I represent Advanced Micro Devices, Inc. MR. HOUSTON: This is Michael Houston of Foley & Lardner representing Renesas Electronics Corporation	6 7 8 9 10 11	all petitioners, to avoid having us having to make duplicate objections. MR. LAHAV: And we agree with that. And if we could actually limit it to statements from Mr. Fitzpatrick that would be best, but
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6 7 9 10 11 12 13 14 15	MR. ZHOU: Yes, this is Xin-Yi Zhou. It's spelled X-I-N dash Y-I, and the last name is Z-H-O-U, and I represent Advanced Micro Devices, Inc. MR. HOUSTON: This is Michael Houston of Foley & Lardner representing Renesas Electronics Corporation and Renesas Electronics America, Inc., Renesas being spelled R-E-N-E-S-A-S, for the	6 7 9 10 11 12 13 14 15	all petitioners, to avoid having us having to make duplicate objections. MR. LAHAV: And we agree with that. And if we could actually limit it to statements from Mr. Fitzpatrick that would be best, but MR. FITZPATRICK: Our intention is to try to do that to the extent possible. MR. LAHAV: Okay. Thank you.
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6 7 9 10 11 12 13 14 15 16 17 18	MR. ZHOU: Yes, this is Xin-Yi Zhou. It's spelled X-I-N dash Y-I, and the last name is Z-H-O-U, and I represent Advanced Micro Devices, Inc. MR. HOUSTON: This is Michael Houston of Foley & Lardner representing Renesas Electronics Corporation and Renesas Electronics America, Inc., Renesas being spelled R-E-N-E-S-A-S, for the court reporter. MR. SILLIMAN: Michael Silliman here, last name is S-I-L-L-I-M-A-N, from	6 7 9 10 11 12 13 14 15 16 17 18	all petitioners, to avoid having us having to make duplicate objections. MR. LAHAV: And we agree with that. And if we could actually limit it to statements from Mr. Fitzpatrick that would be best, but MR. FITZPATRICK: Our intention is to try to do that to the extent possible. MR. LAHAV: Okay. Thank you. EXAMINATION BY MR. LAHAV: Q. Good morning.
6 7 9 10 11 12 13 14 15 16 17 18 19	MR. ZHOU: Yes, this is Xin-Yi Zhou. It's spelled X-I-N dash Y-I, and the last name is Z-H-O-U, and I represent Advanced Micro Devices, Inc. MR. HOUSTON: This is Michael Houston of Foley & Lardner representing Renesas Electronics Corporation and Renesas Electronics America, Inc., Renesas being spelled R-E-N-E-S-A-S, for the court reporter. MR. SILLIMAN: Michael Silliman here, last name is S-I-L-L-I-M-A-N, from Baker, Botts, LLP, representing Toshiba.	6 7 9 10 11 12 13 14 15 16 17 18 19	all petitioners, to avoid having us having to make duplicate objections. MR. LAHAV: And we agree with that. And if we could actually limit it to statements from Mr. Fitzpatrick that would be best, but MR. FITZPATRICK: Our intention is to try to do that to the extent possible. MR. LAHAV: Okay. Thank you. EXAMINATION BY MR. LAHAV: Q. Good morning. A. Good morning.
6 7 9 10 11 12 13 14 15 16 17 18 19 20	MR. ZHOU: Yes, this is Xin-Yi Zhou. It's spelled X-I-N dash Y-I, and the last name is Z-H-O-U, and I represent Advanced Micro Devices, Inc. MR. HOUSTON: This is Michael Houston of Foley & Lardner representing Renesas Electronics Corporation and Renesas Electronics America, Inc., Renesas being spelled R-E-N-E-S-A-S, for the court reporter. MR. SILLIMAN: Michael Silliman here, last name is S-I-L-L-I-M-A-N, from Baker, Botts, LLP, representing Toshiba. THE VIDEOGRAPHER: And would the	6 7 9 10 11 12 13 14 15 16 17 18 19 20	all petitioners, to avoid having us having to make duplicate objections. MR. LAHAV: And we agree with that. And if we could actually limit it to statements from Mr. Fitzpatrick that would be best, but MR. FITZPATRICK: Our intention is to try to do that to the extent possible. MR. LAHAV: Okay. Thank you. EXAMINATION BY MR. LAHAV: Q. Good morning. A. Good morning. Q. Can you please state your full name for the
6 7 9 10 11 12 13 14 15 16 17 18 19 20 21	MR. ZHOU: Yes, this is Xin-Yi Zhou. It's spelled X-I-N dash Y-I, and the last name is Z-H-O-U, and I represent Advanced Micro Devices, Inc. MR. HOUSTON: This is Michael Houston of Foley & Lardner representing Renesas Electronics Corporation and Renesas Electronics America, Inc., Renesas being spelled R-E-N-E-S-A-S, for the court reporter. MR. SILLIMAN: Michael Silliman here, last name is S-I-L-L-I-M-A-N, from Baker, Botts, LLP, representing Toshiba. THE VIDEOGRAPHER: And would the court reporter please swear in the witness.	6 7 9 10 11 12 13 14 15 16 7 8 9 20 21	all petitioners, to avoid having us having to make duplicate objections. MR. LAHAV: And we agree with that. And if we could actually limit it to statements from Mr. Fitzpatrick that would be best, but MR. FITZPATRICK: Our intention is to try to do that to the extent possible. MR. LAHAV: Okay. Thank you. EXAMINATION BY MR. LAHAV: Q. Good morning. A. Good morning. Q. Can you please state your full name for the record.
6 7 9 10 11 12 13 14 15 16 17 18 20 21 22	MR. ZHOU: Yes, this is Xin-Yi Zhou. It's spelled X-I-N dash Y-I, and the last name is Z-H-O-U, and I represent Advanced Micro Devices, Inc. MR. HOUSTON: This is Michael Houston of Foley & Lardner representing Renesas Electronics Corporation and Renesas Electronics America, Inc., Renesas being spelled R-E-N-E-S-A-S, for the court reporter. MR. SILLIMAN: Michael Silliman here, last name is S-I-L-L-I-M-A-N, from Baker, Botts, LLP, representing Toshiba. THE VIDEOGRAPHER: And would the court reporter please swear in the witness. DR. UWE KORTSHAGEN,	6 7 9 10 11 12 13 14 15 16 17 18 9 20 21 22	all petitioners, to avoid having us having to make duplicate objections. MR. LAHAV: And we agree with that. And if we could actually limit it to statements from Mr. Fitzpatrick that would be best, but MR. FITZPATRICK: Our intention is to try to do that to the extent possible. MR. LAHAV: Okay. Thank you. EXAMINATION BY MR. LAHAV: Q. Good morning. A. Good morning. Q. Can you please state your full name for the record. A. My full name is Uwe Richard Kortshagen.
6 7 8 9 10 11 12 13 14 15 16 17 18 9 20 21 22 23	MR. ZHOU: Yes, this is Xin-Yi Zhou. It's spelled X-I-N dash Y-I, and the last name is Z-H-O-U, and I represent Advanced Micro Devices, Inc. MR. HOUSTON: This is Michael Houston of Foley & Lardner representing Renesas Electronics Corporation and Renesas Electronics America, Inc., Renesas being spelled R-E-N-E-S-A-S, for the court reporter. MR. SILLIMAN: Michael Silliman here, last name is S-I-L-L-I-M-A-N, from Baker, Botts, LLP, representing Toshiba. THE VIDEOGRAPHER: And would the court reporter please swear in the witness. DR. UWE KORTSHAGEN, a witness in the above-entitled action,	6 7 8 9 10 11 12 13 14 15 16 17 18 9 20 21 22 23	all petitioners, to avoid having us having to make duplicate objections. MR. LAHAV: And we agree with that. And if we could actually limit it to statements from Mr. Fitzpatrick that would be best, but MR. FITZPATRICK: Our intention is to try to do that to the extent possible. MR. LAHAV: Okay. Thank you. EXAMINATION BY MR. LAHAV: Q. Good morning. A. Good morning. Q. Can you please state your full name for the record. A. My full name is Uwe Richard Kortshagen. Q. And can you spell all of that.
6 7 9 10 11 12 13 14 15 16 17 18 20 21 22	MR. ZHOU: Yes, this is Xin-Yi Zhou. It's spelled X-I-N dash Y-I, and the last name is Z-H-O-U, and I represent Advanced Micro Devices, Inc. MR. HOUSTON: This is Michael Houston of Foley & Lardner representing Renesas Electronics Corporation and Renesas Electronics America, Inc., Renesas being spelled R-E-N-E-S-A-S, for the court reporter. MR. SILLIMAN: Michael Silliman here, last name is S-I-L-L-I-M-A-N, from Baker, Botts, LLP, representing Toshiba. THE VIDEOGRAPHER: And would the court reporter please swear in the witness. DR. UWE KORTSHAGEN,	6 7 9 10 11 12 13 14 15 16 17 18 9 20 21 22	all petitioners, to avoid having us having to make duplicate objections. MR. LAHAV: And we agree with that. And if we could actually limit it to statements from Mr. Fitzpatrick that would be best, but MR. FITZPATRICK: Our intention is to try to do that to the extent possible. MR. LAHAV: Okay. Thank you. EXAMINATION BY MR. LAHAV: Q. Good morning. A. Good morning. Q. Can you please state your full name for the record. A. My full name is Uwe Richard Kortshagen.

3 (Pages 6 to 9)

DR. UWE KORTSHAGEN is K-O-R-T-S-H-A-G-E-N. Q. Have you ever given a deposition before? A. No. Q. Okay. So I'm going to go over some of the rules of depositions, okay? A. Thank you. Q. Do you understand that you've just taken an oath to testify truthfully? A. Yes. Q. And you will testify truthfully today? A. Yes. Q. You understand that I'm going to be asking you questions? A. Yes. Q. And that you have an obligation to answer my questions? A. Yes. Q. And that even if your counsel objects to my questions, you still have to answer them; do you understand that? A. Yes.	$ \begin{array}{c} 1\\2\\3\\4\\5\\6\\7\\8\\9\\0\\11\\2\\13\\4\\5\\16\\7\\8\\9\\0\\21\\22\\22\end{array} $	 DR. UWE KORTSHAGEN A. Yes. Q. Please allow me to finish my question before you answer, okay? A. Yes. Q. Thank you. If you don't understand a question or you would like me to rephrase, please ask me to do so, okay? A. Yes. Q. If I ask a question and you answer it, I'm going to assume you understood it. Is that fair? A. Yes. Q. Okay. Please also be careful to give audible, verbal answers to my questions, all right? A. Yes. Q. So uh-huhs or nuh-uhs, the court reporter has trouble taking those, so it's important to give the verbal answers, all right? A. Yes.
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questions, you still have to answer them; do you understand that?	20 21	give the verbal answers, all right? A. Yes.
you understand that?	21	A. Yes.
-		
A. 16S.	62	
The one expension to that is if you get		Q. Are you taking any medications that might
		impair your ability to testify truthfully
• •		today?
attorney/chent privilege; do you understand?	2.5	A. No.
Page 12		Page 13
DR. UWE KORTSHAGEN	1	DR. UWE KORTSHAGEN
Q. Is there any other reason why you can't	2	Q. What was the topic of that dissertation?
	3	A. The topic was on electron energy distribution
A. No.	4	functions in radio frequency produced
Q. Okay. Where are you currently employed?	5	plasmas.
A. At the University of Minnesota.	6	Q. Did you study any particular applications?
Q. And what is your title?	7	A. I studied a particular method of generating
A. I'm a professor of mechanical engineering.	8	plasmas based on so-called propagating
Q. In your CV you reference a diploma degree in	9	surface waves.
physics in June of 1988, and it's how do	10	Q. And did you did you study any particular
you pronounce the name of the university?	11	commercial application or application of any
A. The University of Bochum.	12	particular endeavor other than the
Q. Bochum?	13	generalized generation of plasmas?
A. Bochum.	14	A. No.
Q. Bochum. And is a diploma degree like a	15	Q. Okay. Did that dissertation entail research
bachelor's degree in the United States?	16	relating to generation of plasmas inside a
A. It is probably between a bachelor's and a	17	magnetron?
master's degree. It is a five-year degree.	18	A. No.
Q. Okay. Did you okay. And then you	19	Q. Did you study in your dissertation generating
obtained a Ph.D. in January of 1991 from the	20	plasmas for purposes of sputtering?
same university?	21	A. No.
A. That is correct, yes.	22	Q. After your Ph.D., under education your CV
	23	lists a, quote, habilitation in experimental
	24	physics?
A. Yes, I did.	25	A. That is correct.
	 DR. UWE KORTSHAGEN Is there any other reason why you can't testify truthfully today? No. Okay. Where are you currently employed? At the University of Minnesota. And what is your title? I'm a professor of mechanical engineering. In your CV you reference a diploma degree in physics in June of 1988, and it's how do you pronounce the name of the university? The University of Bochum. Bochum? Bochum. Bochum. And is a diploma degree like a bachelor's degree in the United States? It is probably between a bachelor's and a master's degree. It is a five-year degree. Okay. Did you okay. And then you obtained a Ph.D. in January of 1991 from the same university? That is correct, yes. Did you prepare a dissertation in connection with your Ph.D.? 	instructed on attorney work product or attorney/client privilege; do you understand? 25 Page 12 DR. UWE KORTSHAGEN 1 2. Is there any other reason why you can't testify truthfully today? 3 4. No. 4 2. Okay. Where are you currently employed? 5 4. At the University of Minnesota. 6 2. And what is your title? 7 4. I'm a professor of mechanical engineering. 8 2. In your CV you reference a diploma degree in 9 physics in June of 1988, and it's how do 10 you pronounce the name of the university? 11 4. The University of Bochum. 12 2. Bochum? 13 4. Bochum. 14 2. Bochum. 14 3. Bochum. 14 3. Bochum. 14 4. It is probably between a bachelor's and a 17 master's degree. It is a five-year degree. 18 2. Okay. Did you okay. And then you 19 obtained a Ph.D. in January of 1991 from the 20 same university? 21 4. That is correct, yes. 22 2. Did you prepare a dissertation in connection 23 with your Ph.D.? 24

4 (Pages 10 to 13)

	Page 14		Page 15
1	DR. UWE KORTSHAGEN	1	DR. UWE KORTSHAGEN
2	Q. What is a habilitation in experimental	2	sputtering?
3	physics?	3	A. Yes.
4	A. Habilitation is a specific degree in the	4	Q. Did it include plasmas used for magnetron
5	German academic system which at that time in	5	sputtering?
6	the 1990s was required to become a.	6	A. No.
7	university professor.	7	Q. Can you explain the work you did in
8	Q. Does it correlate with post-doc research?	8	connection with your habilitation related to
9	A. Yeah, you may correlate it with with an	9	plasmas used for sputtering?
10	advanced post doc. It also includes writing	10	A. Among other among the different systems
11	yet another thesis, habilitation, but one is	11	that I studied at that time was a particular
12	already in the position to advise Ph.D.	12	plasma system called capacitively coupled
13	students at that point.	13	plasma, and such kinds of plasmas can be used
14	Q. Was there any coursework required	14	for the chemical vapor deposition of films,
15	A. No, there is no	15	but they can also be used for sputtering.
16	Q. Go ahead.	16	Q. And sputtering is not chemical vapor
17	A. No, there is no coursework required.	17	deposition, correct?
18	Q. What was the topic of your thesis for your	18	A. I would call it more physical vapor
19	habilitation?	19	deposition.
20 01	A. The topic of the thesis was on kinetic theory	20 21	Q. So sputtering is physical vapor deposition
21 22	and experiments studying electron	21 22	and chemical vapor deposition is some other
23	distribution functions in a wide range of	22 23	process, right?
24 24	plasmas. Q. In that, quote, "wide range of plasmas," end	2.4	A. Could you repeat that question, please?Q. Sure. I'm not going to repeat it, I'm going
25	quote, did that include plasmas used for	25	to change it.
		+	
	Page 16		Page 17
1	DR. UWE KORTSHAGEN	1	DR. UWE KORTSHAGEN
2	When when people in the art talk about	2	Q. Did you apply them?
2 3	When when people in the art talk about chemical vapor deposition, that's something	2 3	Q. Did you apply them? MR. FITZPATRICK: Objection to the
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2 3 4 5 6 7 8	When when people in the art talk about chemical vapor deposition, that's something different than sputtering, correct?A. Generally, I would say this is correct, yes.Q. So you said you studied this capacitively? coupled plasmas that could be used for sputtering. Did you study them in connection	2 3 4 5 6 7 8	 Q. Did you apply them? MR. FITZPATRICK: Objection to the form of the question. THE WITNESS: If you're asking me whether I applied what I learned at the time. to sputtering, the answer is no. BY MR. LAHAV:
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$\begin{array}{c} 2\\ 3\\ 4\\ 5\\ 6\\ 7\\ 8\\ 9\\ 0\\ 1\\ 1\\ 2\\ 3\\ 4\\ 1\\ 5\\ 6\\ 7\\ 8\\ 9\\ 0\\ 1\\ 1\\ 2\\ 0\\ 2\\ 1\\ 2\\ 0\\ 2\\ 1\end{array}$	 When when people in the art talk about chemical vapor deposition, that's something different than sputtering, correct? A. Generally, I would say this is correct, yes. Q. So you said you studied this capacitively? coupled plasmas that could be used for sputtering. Did you study them in connection with their use for sputtering? A. I studied them with respect to their how should I express it with respect to the properties of electrons within these plasmas, in particular, the energy distribution function of electrons. Q. But you didn't study how to make use of that energy distribution function with respect to sputtering, correct? MR. FITZPATRICK: Objection to the form of the question. THE WITNESS: I think the correct way to answer this is to say that the fundamental studies of electron distribution functions that I performed also applied to 	2 3 4 5 6 7 8 9 10 11 12 13 14 15 16 17 18 9 20 21 22 23	 Q. Did you apply them? MR. FITZPATRICK: Objection to the form of the question. THE WITNESS: If you're asking me whether I applied what I learned at the time. to sputtering, the answer is no. BY MR. LAHAV: Q. Did you study how those plasmas might be used for sputtering? A. No. Q. Do you have any industry experience? Have you ever worked in industry? A. No. Q. Have you ever operated a PVD apparatus? A. No. Q. So you've never operated a magnetron sputtering chamber, for example, right? A. No. Q. Have you ever designed a magnetron sputtering chamber? A. No. Q. The focus of your research with respect to
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